



IIT Bombay Nanofabrication Facility

Tool Name: ICPRIE - Dia

Training and Usage Policy

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Version 1.0

Updated on: 13 April 2026

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Training & Usage Policy:

- The tool category is semi clean A
- Allowed materials for etching are restricted to Si, SiN, SiO₂, SiC and Diamond for the initial time period.
- Only Photoresist is allowed as hard mask
- Other group IV materials need to be discussed with FIC for approval and usage.
- If the sample is processed from outside IITBNF (Completely/partially) the sample would be an external sample and would need contamination check as well as process approvals from FIC and Process Committee for usage in ICPRIE – Dia.
- To start with, one user per group will be trained.
- The IITBNF users can send training requests for authorization.
- Minimum 1 eyes-on and 2 hands-on training sessions are required before the authorization test.
- AUs will be assigned training responsibilities as per the training needs. In addition, AUs may be asked to do process runs for others (in case of non-availability of operators).
- Authorized users are expected to take care of process runs of other users from the same group.
- Please note that violation of any of the above policies will attract penalties amounting to de-authorization for up to 30 days.
- Once in a month the tool will be blocked for the baseline of the tool.